Lithographic Apparatus and Device Manufacturing Method

ABSTRACT

A lithographic apparatus includes an illumination system for projecting a beam of radiation onto a substrate. The lithographic apparatus further has a chuck assembly for supporting at least one of the substrate or a patterning device, the patterning device serving to impart the beam with a pattern in its cross-section. A heat transfer system is operable between a first surface and a second surface. The heat transfer system is capable of transferring heat between the first surface and the second surface. The first surface is at least partially formed by at least a part of the chuck assembly. The second surface is at least partially formed by at least a part of a component spaced a distance from the chuck. The second surface is mechanically isolated from and thermally coupled to the first surface

Figure 2